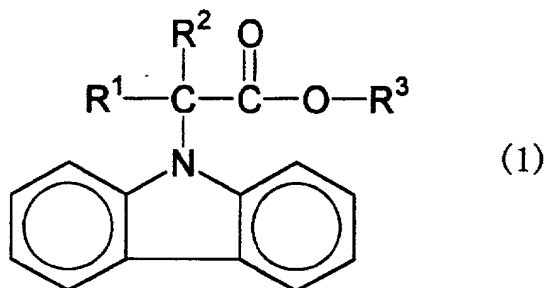


ABSTRACT OF THE DISCLOSURE

A carbazole derivative of the following formula (1),



wherein R¹ and R² individually represent a hydrogen atom or a monovalent organic group, or R¹ and R² form, together with the carbon atom to which R¹ and R² bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and R³ represents a hydrogen atom or a monovalent organic group. The carbazole derivative is suitable as an additive for increasing sensitivity of a chemically amplified resist. A chemically amplified radiation-sensitive resin composition, useful as a chemically amplified resist, comprising the carbazole derivative is also disclosed.

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